

# ISO/TR 16268:2009-10 (E)

## Surface chemical analysis - Proposed procedure for certifying the retained areic dose in a working reference material produced by ion implantation

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<b>Contents</b>		<b>Page</b>
Foreword .....		iv
Introduction .....		v
1	Scope .....	1
2	Normative references .....	1
3	Terms and definitions .....	1
4	Symbols and abbreviated terms .....	5
5	Concept and procedure .....	6
5.1	General information .....	6
5.2	Preparation of the working and transfer reference materials .....	8
5.3	Measurement of retained areic dose in the transfer reference material .....	8
5.4	Compatibility of the working reference material and the surface-analytical method .....	8
6	Requirements .....	9
6.1	Reference materials .....	9
6.2	Instrumentation requirements .....	9
6.2.1	Ion implanter .....	9
6.2.2	Wavelength-dispersive X-ray fluorescence spectrometer .....	9
6.2.3	Electron microprobe .....	10
6.3	Ion-implantation requirements .....	10
6.4	Uniformity requirement .....	10
7	Certification .....	10
7.1	Working reference material against the transfer reference material .....	10
7.2	Transfer reference material against the secondary reference material .....	10
7.3	Retained areic dose of the working reference material .....	11
Annex A (informative)	Ion implantation .....	12
Annex B (informative)	Ion-implantation dosimetry .....	13
Annex C (informative)	X-ray fluorescence spectrometry .....	14
Annex D (informative)	Non-certified secondary reference materials and substitutes .....	15
Annex E (informative)	Uncertainties in measurements of areic dose .....	16
Bibliography .....		19